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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Robert W. Corrigan et al.

Serial No.: 09/832,738

Filed: April 10, 2001

For:

METHOD, SYSTEM AND DISPLAY APPARATUS FOR

ENCRYPTED CINEMA

Group Art Unit: 2643

Examiner:

TRANSMITTAL LETTER

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Respectfully submitted,

HAVERSTOCK & OWENS LLP

Dated: 7-16-63

Thomas B. Haverstock

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- U.S. Patent No. Des. 334,557;
- U.S. Patent No. Des. 334,742;
- U.S. Patent No. Des. 337,320;
- U.S. Patent No. Re. 16,767;
- U.S. Patent No. Re. 25,169;
- German Publication No. DE 32 33 195 A1;
- German Publication No. DE 43 23 799 A1;
- German Publication No. DE 197 23 618 A1;

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- German Publication No. DE 198 46 532 C1;
- European Publication No. EP 0 089 044 A2;
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Respectfully submitted,

HAVERSTOCK & OWENS LLP

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